

In the Specification:

Please enter the enclosed new Abstract.

Please replace par. [0001] as follows:

The invention relates to a gas discharge source ~~as claimed in the preamble of claim 4.~~ Preferred application area are those requiring extreme ultraviolet and/or soft X-radiation in the wavelength range from approximately 1 nm to 20 nm, such as, in particular, semiconductor lithography.

Please delete par. [0008].